

L Number	Hits	Search Text	DB	Time stamp
1	350	(438/704).CCLS.	USPAT; US-PGPUB	2004/07/08 13:42
2	159	((438/704).CCLS.) and silicon with ((oxide dioxide) and nitride)	USPAT; US-PGPUB	2004/07/08 13:43
3	80	((438/704).CCLS.) and silicon with ((oxide dioxide) and nitride)) and (oxide dioxide) with (dry plasma anisotropic) with (etch\$4)	USPAT; US-PGPUB	2004/07/08 13:44
4	14	((438/704).CCLS.) and silicon with ((oxide dioxide) and nitride)) and (oxide dioxide) with (dry plasma anisotropic) with (etch\$4)) and (nitride) with (wet with etch\$4)	USPAT; US-PGPUB	2004/07/08 13:44